Packaging with double-side cooling capability for SiC devices, based on silver sintering IECON 2018

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Introduction

Manufacturing of the 3-D structure

Results

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Double Side Cooling



- SiC JFETs (or MOSFETs) sensitive to thermal run-away
- → Need for efficient cooling, despite high temperature capability
- Standard packaging offers cooling through one side of the die only
- "Sandwich" package performs thermal management on both sides
- Requires special features for topside contact



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The proposed 3-D Structure



- Two ceramic substrates, in "sandwich" configuration
- ► Two SiC JFET dies (SiCED)
- Assembled using silver sintering
- 25.4 mm×25.4 mm (1 in×1 in)



Ceramic Substrates

Scale drawing for 2.4×2.4 mm² die



- Etching accuracy exceeds standard design rules
- Double-step copper etching for die contact
- → Custom etching technique





plain DBC board

- ► Final patterns within 50 µm of desired size
- ▶ Two designs, for 2.4 mm and 4 mm dies
 - Die top metallized (PVD) with Ti/Ag
- Total copper thickness 300 μ m, \approx 150 μ m per step







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3b - Exposure and Developpment



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Bonding Material: Silver Sintering



Göbl, C. et al "Low temperature sinter technology Die attachment for automotive power electronic applications" proc of APE, 2006

Silver Paste

- Based on micro-scale silver particles (Heraeus LTS-117O2P2)
- ► Low temperature (240 °C) sintering
- Low pressure (2 MPa) process

No liquid phase involved:

- No movement of the die
- No bridging across terminals
- No height compensation thanks to wetting









Screen printing

- Ceramic jigs for alignment of dies and substrate
- Pre-drying of paste to prevent smearing
- Two sintering steps using the same temperature profile





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2- Mounting in alignment jig

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6 - Screen printing on "drain" substrate

- Ceramic jigs for alignment of dies and substrate
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- Very good form factor, especially around gate contact
- Uniform silver layers
- Encapsulation with parylene HT (not shown here)





- Contact on Gate, Source and Drain of all JFETs
- No short-circuit between contacts



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SD structure using only high-temperature-rated materials Should be able to operate continuously at 300 ℃

- Silver sintering is suited to rigid sandwich structures.
- Proposed etching technique offers satisfying resolution
- Package for demonstration of technology, no cooling attempted yet
 - Current structure fragile, new modules should integrate mechanical reliefs (solid encapsulant, direct substrate-substrate bonding...)



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Thank you for your attention.





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